

VE320 Intro to Semiconductor Devices

Summer 2024 – Problem Set 8

Due: 11:59pm, August 2nd

In all problems, assume the temperature is 300K, all are completely ionization and the semiconductor material is Si and oxide material is SiO₂.

1. Discuss why the threshold voltage changes when a reverse-biased source-to-substrate voltage is applied to a MOSFET.
What is subthreshold conduction? Sketch a drain current versus gate voltage plot that shows the subthreshold current for the transistor biased in the saturation region.
What is channel length modulation? Sketch an I–V curve that shows the channel length modulation effect.
2. A p-channel MOSFET has the following parameters: $k_p' = 0.10\text{mA/V}^2$, $W/L = 15$, and $V_T = -0.4\text{V}$. Calculate the drain current I_D for (a) $V_{SG} = 0.8\text{V}$, $V_{SD} = 0.25\text{V}$; (b) $V_{SG} = 0.8\text{V}$, $V_{SD} = 1.0\text{V}$; (c) $V_{SG} = 1.2\text{V}$, $V_{SD} = 1.0\text{V}$; and (d) $V_{SG} = 1.2\text{V}$, $V_{SD} = 2.0\text{V}$.
3. An ideal n-channel MOSFET has the following parameters: $V_T = 0.45\text{V}$, $\mu_n = 425\text{cm}^2/\text{Vs}$, $t_{\text{ox}} = 11\text{nm}$, $W = 20\mu\text{m}$, and $L = 1.2\mu\text{m}$. (a) Plot I_D vs V_{DS} for $0 \leq V_{DS} \leq 3\text{V}$ and for $V_{GS} = 0, 0.6, 1.2, 1.8$, and 2.4V . Indicate on each curve the $V_{DS}(\text{sat})$ point. (b) Plot $\sqrt{I_D(\text{sat})}$ vs V_{GS} for $0 \leq V_{GS} \leq 2.4\text{V}$. (c) Plot I_D vs V_{GS} for $0 \leq V_{GS} \leq 2.4\text{V}$ and for $V_{DS} = 0.1\text{V}$.
4. The substrate doping and body-effect coefficient of an n-channel MOSFET are $N_a = 10^{16}\text{cm}^{-3}$ and $\gamma = 0.12\text{V}^{0.5}$, respectively. The threshold voltage is found to be $V_T = 0.5\text{V}$ when biased at $V_{SB} = 2.5\text{V}$. What is the threshold voltage at $V_{SB} = 0\text{V}$?
5. A silicon n-channel MOSFET has a doping concentration of $N_a = 2 \times 10^{16}\text{cm}^{-3}$ and a threshold voltage of $V_T = 0.40\text{V}$. Determine the change in channel length, ΔL , for (a) $V_{GS} = 1.0\text{V}$, $V_{DS} = 2.0\text{V}$; (b) $V_{GS} = 1.0\text{V}$, $V_{DS} = 4.0\text{V}$; (c) $V_{GS} = 2.0\text{V}$, $V_{DS} = 2.0\text{V}$; and (d) $V_{GS} = 2.0\text{V}$, $V_{DS} = 4.0\text{V}$.
6. For a long channel NMOSFET with $V_T = 1\text{V}$, calculate the V_{GS} required for an $I_D(\text{sat.})$ of 0.1mA and $V_{DS}(\text{sat.})$ of 5V . Calculate the small-signal output conductance g and the transconductance $g_m(\text{sat.})$ at $V_{DS} = 10\text{V}$. Sketch the cross section of this MOSFET, and for $V_{DS} = 1\text{V}$, 5V , and 10V . (V_G is constant in this problem)

7. The subthreshold current in a MOSFET is given by $I_D = I_S e^{\frac{V_{GS}}{nV_t}}$. Determine the change in applied V_{GS} for a factor of 10 increase in I_D for (a) $n = 1$; (b) $n = 1.5$, and (c) $n = 2.1$.